

Contract Final Report For
Development of High Temperature, High
Radiation Resistant Silicon Semiconductors

Ref. DCN 1-0-40-02692
Contract # NAS8-25917

Submitted to:

George C. Marshall Space Flight Center
National Aeronautics & Space Administration
Marshall Space Flight Center
Huntsville, Alabama 35812

Submitted by:

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Project Manager

(NASA-CR-124074) - DEVELOPMENT OF HIGH
TEMPERATURE, HIGH RADIATION RESISTANT
SILICON SEMICONDUCTORS Contract Final
Report (Solitron Devices, Inc., Riviera
Beach, Fla.) 65 p HC \$5.25 CSCL 20L

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I. OBJECTIVE

The objective of this contract is to design, develop and fabricate a hardened power transistor that will meet or exceed the performance requirements of future electronic systems that must operate in severe nuclear space radiation environments.

Many space and missile programs are limited by the susceptibility of semiconductors to radiation damage. Of the semiconductor devices, power transistors are usually the most difficult to harden and therefore limit the hardness of an electronic system. There are now a number of design and processing techniques that can be applied to improve their post-radiation gain, saturation voltage and second breakdown characteristics for a range of currents and voltages.

Today, silicon planar transistors can be expected to degrade but to retain useful performance characteristics in the range of 1×10^{14} n/cm² to 1×10^{15} n/cm², with signal devices remaining capable of operating in the top half of the decade, but with power transistors falling in the bottom half of the decade. Since the gain of power devices after irradiation can now be made comparable to signal devices for large applied voltages by shallow base diffusion, the proposed effort concentrates on the additional requirements for power transistors of gain fall-off at high currents, saturation voltage and high temperature performance.

II. Device Hardness and Diffusion Technique

Past experience in the field of radiation hardened devices indicates that current gain is the key parameter to be considered in hardening transistors. A model which relates changes in gain to neutron fluence levels is expressed by:

$$\frac{1}{h_{FEp}} - \frac{1}{h_{FEo}} = K\tau_B (Q_2 - Q_1)$$

which is an expression of the gain degradation $\frac{1}{h_{FEp}} - \frac{1}{h_{FEo}}$

as a function of:

- a) the radiation fluence level ($Q_2 - Q_1$)
- b) the base transit time (τ_B)
- c) the radiation damage factor K.

Of these factors the only one with which the designer has any real freedom is the base transit time τ_B .

$$\tau_B = \frac{W^2}{2 D_{nB}} \quad \begin{array}{l} \text{where } W = \text{base width} \\ D_{nB} = \text{Diffusion Const.} \\ \text{for electrons in base.} \end{array}$$

The main objective is to minimize the base transit time τ_B by controlling the base width of the device. This dimension can only be optimized to the limit of the voltage requirement of the application. Some effect on τ_B can also be had by changing the diffusion constant D_{nB} by various base doping modifications. Lower base concentrations tend to decrease D_{nB} but will also lower the maximum operating voltage of the device.

In order to obtain the intrinsic base transit time the gain bandwidth product must be measured at different current levels in the linear region and plotted. However, using f_t as the parameter to obtain the base transit time is not completely accurate.

From the expression

$$\frac{1}{2\pi f_t} = \frac{1}{KQ} \frac{KT}{qI_e} (C_{TE} + C_{TC}) + \frac{B}{2.43}$$

it can be seen that f_t is also a function of the emitter and collector junction Capacitances while τ_B is a physical property of the base.

The direct measurement of the base width W_B is a better indicator of τ_B than the above method. The Solitron device hardness is achieved by maximum base width control. Production lots are limited in size and one wafer is used as a control, this wafer is sectioned after base and emitter diffusion. The base width is measured by interference technique. Using these techniques the base width can be controlled quite easily. The devices will be double diffused NPN Silicon types. Because of the narrow highly doped base region required shallow diffusion techniques will be necessary. Solitron is using its programmed emitter diffusion techniques for these devices. This technique affords maximum reproducibility to the process. It is estimated that a base width W_B of approximately $.3\mu$ and a base doping of about 3×10^{18} atoms/cc will be needed to meet the transistor design goals of breakdown voltage and gain.

III. SCOPE OF WORK

A. 100 Ampere Transistor

Three geometries were investigated to determine which one would be best for the 100 ampere operation. The chips were designated as the 7R, 8R and 8R-DA. The geometrical details are shown in table 1.

Chip Type	Die Size (mils)	Base area (mils) ²	Emitter area (mils) ²	Emitter periphery (mils)	EP/EA
7R	140 x 170	10,912	4,800	5,040	1.05
8R	266 x 276	57,584	29,776	5,674	0.19
8R-DA	244 x 213	40,953	18,271	2,408	0.13
3R	80 x 120	6,370	1,602	3,612	0.45
6R	120 x 160	12,740	3,204	7,224	0.45

Table 1

Geometrical Details of Hardened Power Transistor Chips.

The 8R chip geometry did not produce any devices suitable to the 100 amp application. It was found that the base area was too large to support the shallow diffusion (1.5μ - 1.9μ) necessary for radiation resistance. The problem was that any type of microscopic contamination would mask the diffusion causing low breakdown voltages or collector to emitter shorts after the emitter was diffused. This type of problem is not as critical for normal power devices because the deep base diffusions ($\approx 10\mu$) in most cases will diffuse under microscopic contamination and wipe out its effect. The same problem was experienced with the 8R-DA chip. The base area was just too large to support the radiation type diffusion.

The 7R chip geometry proved more feasible due to the smaller total area and the design of the chip. It incorporates two bases diffused into the chip which made up the total area. This kept the possibility of microscopic contamination to a minimum and a successful radiation type diffusion was accomplished.

This 7R geometry incorporates an interdigitated structure of sixty emitter stripes each forty mils in length and one mil in width. This is to maximize the device emitter periphery in

order to minimize the phenomenon of emitter edge injection at high current levels which would cause excessive gain degradation when subjected to a high energy neutron environment.

The radiation type diffusion that was originally proposed was for a base width of approximately 0.3U. This base width, however, was found to be too narrow for a large area device to yield any transistors with a 90 volt BVceo. In order to sustain this breakdown voltage, the base width had to be increased to a range of 0.6 μ to 0.8 μ . This range should be adequate for a neutron flux density in the upper decade of the range from 1×10^{14} n/cm² to 1×10^{15} n/cm².

Since the 7R chip is a 25 Amp chip, it was proposed that this chip would be used as a unit cell and that the 100 amp capability would be accomplished by paralleling a number of these chips to reach the required capability. This is common practice in the power transistor field, however, care must be exercised to match the chips for BVceo and gain. The chips for this contract were matched for BVceo within five volts and the gain was matched within 5% at 5 volts/500 ma.

Devices were assembled to ascertain the number of chips needed in parallel to reach the 100 amp capacity. Six units with two chips were assembled and four units with three chips were assembled, all in the TO-114 package. Electrical tests indicated that the best that could be expected from these devices was 70 amp operation (see data) at room temperature. Since the TO-114 package will not hold more than three chips comfortably, it was decided to try the HKCG motor control package which was in development for a NASA project and would accept a greater number of chips. A one month delay was experienced in this portion of the project waiting for a package to become available.

An HKCG motor control package was assembled with four chips in parallel. This assembly did not meet the 100 Amp requirement due to contamination of a source gas during fabrication. No other packages were available at this time and a three months delay in this portion of the project was experienced before more packages became available. It should be noted that Solitron was

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TEST DATA SHEET

TYPE 7R LOT NO. 4 LOT SIZE _____ SAMPLE SIZE _____

RELIABILITY ☐ PAGE 1 OF 1

CUSTOMER NASA CUSTOMER P. O. _____ TESTER _____

PRE-SHIP INSP. ☐

FINAL INSP. ☐ DATE _____

[illegible]

fabricating these packages from raw materials for another NASA contract which had priority on their availability.

When the package problem eased, assembly procedures were started again. No problems were encountered in mounting the chips in the package but problems were experienced in hermetically sealing the package. The method of sealing that was used was to braze the cap onto the package utilizing a gold-germanium preform at 385°C in a hydrogen atmosphere. It was found that the hydrogen was absorbed in the oxide surface of the chip causing an inversion type surface electrical leakage. The unit recovered when the cap was removed and then vacuum baked at 300°C .

The obvious method of correcting this problem, that of coating the transistor chips with a silicone resin, is not feasible as the resin will not withstand a high radiation fluence level. However, a package consisting of six chips in the HKCG motor control package was assembled with varnish coating in order to secure electrical data. The device was tested for H_{FE} , $V_{CE}(\text{sat})$ and $V_{BE}(\text{sat})$ in increments up to 120 amps (see data). The device was destroyed in attempting to test above 120 amps.

Since the HKCG package presented sealing problems, six low voltage chips were assembled in a TO-68 weldable package and tested for 100 amp capability at room temperature. The tests on this unit was favorable so assembly was begun on the twenty devices to satisfy the terms of the contract.

It was found that this package configuration would support 90 Volt $V_{CE0}(\text{sus})$ at 100 amps but would fail randomly at higher temperatures. The maximum temperature achieved before failure was 210°C and the minimum was 125°C . Ten of these devices were submitted to NASA-MSFC for critical analysis. The mechanism appears to be thermal stress causing the weakest chip to go into secondary breakdown. This causes the current load to avalanche to the other chips causing complete destruction.

It was felt that a redesign of the package was necessary. The proposed package would incorporate eight transistor chips to further reduce the load on each individual chip and a much heavier copper base than the TO-68 to help dissipate the heat from the chips.

TEST DATA SHEET

FINAL INSP. 0 DATE 6-16-71

[illegible]

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TEST DATA SHEET

EVALUATION SAMPLES SES 2410

TYPE 100 AMI² LOT NO. _____ LOT SIZE _____ SAMPLE SIZE _____

RELIABILITY ☐ PAGE 1 OF 2

CUSTOMER NAS 9 CUSTOMER P. O. NAS-25911 TESTER _____

PRE-SHIP INSP. ☐

FINAL INSP. ☐ DATE _____

[illegible]

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TEST DATA SHEET

EVALUATION SAMPLES SES 2410

TYPE 100 REP LOT NO. LOT SIZE SAMPLE SIZE

RELIABILITY ☐ PAGE 2 OF 2

CUSTOMER NASA CUSTOMER P. O. NASA-25917 TESTER _____

PRE-SHIP INSP. ☐

FINAL INSP. ☐ DATE _____

[illegible]

This new package was designed and fabricated and twenty-six devices were assembled for testing. When attempting to test these units for BV_{ceo} (sus), it was found that they were prone to severe oscillation. In fact the oscillation was so severe that it was impossible to test them, even at room temperature, without destroying them. It is felt that the oscillation was caused by the additional wiring made necessary by increasing the number of chips from six to eight since it was not observed on any of the devices previously tested. In addition, some of the chips used to fabricate these devices were from the same diffusion runs that provided chips for the devices in the TO-68 package. Twenty of these devices were submitted to NASA-MSFC to satisfy the requirements of this contract.

Solitron DEVICES, INC.

TRANSISTOR DIVISION

1177 BLUE HERON BLVD., RIVIERA BEACH, FLORIDA 33404

AC - PHONE
305 - 848-4311

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INVOICE
TO

NASA
George C. Marshall Space Flight
Center
Marshall Space Flight Center
Alabama 35812

SHIP TO

SAMS

Accountable Property Officer
Bldg. 4471

TERMS - 1/2% 10, NET 30 DAYS
F.O.B. RIVIERA BEACH, FLORIDA

OUR ORDER NUMBER	CUSTOMER ORDER NUMBER	SHIPPED VIA	REPRESENTATIVE	INVOICE DATE	DATE PROMISED
7-26-72	NAS8-25917	Hand Carry-R. Howard	7-27-72	8-1-72	8-2-72
QUANTITY ORDERED	QUANTITY PACKED	QUANTITY SHIPPED	DESCRIPTION	UNIT PRICE	AMOUNT
20		20	NASA Contract NAS8-25917 ECN 1-0-40-02692, & S1 High Power Transistors with read and record data (Exhibit A, Para. A)		

WE HEREBY CERTIFY THAT THESE GOODS WERE PRODUCED IN COMPLIANCE WITH ALL APPLICABLE REQUIREMENTS OF SECTIONS 1, 7 AND 12 OF THE FAIR LABOR STANDARDS ACT, AS AMENDED, AND OF REGULATIONS AND ORDERS OF THE UNITED STATES DEPARTMENT OF LABOR ISSUED UNDER SECTION 14, THEREOF.
ALL GOODS SHIPPED BY US AT CONSIGNEE'S RISK, AFTER WE HAVE DELIVERED TO TRANSPORTATION COMPANY AND TAKEN RECEIPT FOR SAME.
REJECTION OF ANY SHIPMENT MUST BE REPORTED WITHIN TEN (10) DAYS AFTER RECEIPT OF MATERIAL. THE ABOVE LISTED MERCHANDISE TO REMAIN THE PROPERTY OF SOLITRON DEVICES, INC. UNTIL THE INVOICE IS PAID.

No. T 69427

TYPE 100P/RADIATION LOT NO. _____ LOT SIZE _____ SAMPLE SIZE _____
 CUSTOMER NASA CUSTOMER P.O. _____ TESTER _____

RELIABILITY ☐ PAGE 1 OF 1
 PRE-SHIP INSP. ☐
 FINAL INSP. ☐ DATE 7-13-72

PARAMETER		BV _{CEO}	BV _{ERO}	V _{CE0}	h _{FE}	h _{FE}	h _{FE}	V _{CE(3)}	V _{BE(3)}	V _{CE(3)}	V _{BE(3)}	V _{CE(3)}	V _{BE(3)}
TEMP. 25°C unless noted													
TEST EQUIPMENT NO.													
CONDITIONS		I _C =1.0mA	I _E =1.0mA	I _C =50mA	I _C =50A	I _C =75A	I _C =100A	I _C =50A	I _C =50A	I _C =75A	I _C =75A	I _C =90A	I _C =90A
					V _{CE} =5V	V _{CE} =5V	V _{CE} =5V	I _B =5A	I _B =5A	I _B =7.5A	I _B =7.5A	I _B =9.0A	I _B =9.0A
LIMITS													
MIN.													
MAX.													
UNITS OF MEASURE													
NO.	DATE CODE	V	V	V	h _{FE}	h _{FE}	h _{FE}	V	V	V	V	V	V
2		110	6.0	104	100	73	52	0.36	0.96	0.53	1.05	0.62	1.10
6		110	6.0	96	98	87	55	0.31	0.92	0.53	1.02	0.60	1.05
7		104	6.0	96	105	74	54	0.24	0.94	0.34	1.02	0.40	1.08
8		110	6.0	98	85	64	50	0.31	0.96	0.46	1.05	0.57	1.12
9		118	6.0	108	98	70	52	0.25	0.94	0.36	1.02	0.43	1.10
10		114	5.8	106	85	54	46	0.36	0.96	0.53	1.08	0.62	1.12
11		120	5.8	116	73	80	54	0.42	1.05	0.66	1.18	0.77	1.22
12		62	5.8	114	66	53	45	0.48	1.02	0.66	1.10	0.76	1.15
13		108	6.0	94	102	75	55	0.21	0.92	0.30	1.10	0.36	1.05
15		106	6.0	100	92	64	50	0.30	0.95	0.45	1.05	0.54	1.12
17		124	5.7	118	50	30	18	0.78	1.25	1.15	1.45	1.50	1.60
18		112	5.8	104	90	71	55	0.23	0.93	0.33	1.02	0.38	1.05
19		126	6.0	124	60	48	31	0.35	1.35	0.63	1.60	0.90	1.70
20		112	5.9	104	76	54	46	0.70	1.10	0.94	1.22	1.10	1.30
21		116	5.6	114	65	53	50	0.22	0.92	0.32	1.00	0.38	1.02
22		112	6.0	100	105	65	51	0.42	1.00	0.58	1.12	0.68	1.20
23		85	5.6	108	53	41	28	0.21	0.93	0.32	1.02	0.41	1.08
24		116	5.9	114	82	64	52	0.35	0.96	0.48	1.05	0.58	1.12
25		120	5.9	100	76	53	46	0.55	0.97	0.70	1.08	0.78	1.12
26		120	5.6	96	70	54	48	0.42	0.96	0.57	1.05	0.65	1.10

B. Five Ampere Transistor

The proposed chip to satisfy this portion of the contract was the BR100 chip which is 62.5 mils x 90 mils in size. Upon re-appraisal of the specifications of the contract, it was decided to substitute the BR200 chip which is 80 mils x 120 mils. It was felt that the larger chip would be better able to withstand the stringent environmental conditions.

Sample devices from the initial diffusion run were assembled in the TO-111 package. These units were tested for V_{ceo} (sus) at high temperature using single shot inductive technique. The units failed between 250°C to 260°C. It was felt that the package was too small to adequately dissipate the heat from the chip.

The next several diffusion runs were made attempting to meet the proposed base width of 0.3 μ . It was found that this base width would not support the 90 volt V_{ceo} . By increasing the base width to 0.6 μ the required voltage was sustained.

In order to determine the size package needed to dissipate the heat, the next available chips were mounted in the TO-62 package. These units were tested and the failure range was between 270°C and 290°C. This indicated an improvement over the TO-111 package but the package appears to be inadequate for 300°C operation.

Since going to a larger package increased the temperature response of the chip, additional devices were assembled in the TO-61 package. Two types of devices were fabricated. One type being single chip construction and the other being dual chip construction. These devices were tested for high temperature response and the TO-61 package increased the average temperature capability approximately 5°C over the TO-62 package. It was also noted that the expected difference between the single die construction and the dual die construction did not materialize. Since the dual construction was, in general, slightly lower voltage than the single construction, it was decided to repeat the experiment.

TEST DATA SHEET

YR 50 V.D.
 GRA SEAL FL 33404
 ING 1305V 3-34

TYPE BR200 LOT NO. 3R-1 LOT SIZE 34 SAMPLE SIZE TO-III RELIABILITY ☐ PAGE 1 OF 2
 PRE-SHIP INSP. ☐ CUSTOMER NASA CUSTOMER P.O. NAS8-25917 TESTER N. SQUEO FINAL INSP. ☐ DATE 8-19-70

PARAMETER	V _{CE0}	V _{CE0}	V _{CE0(SUS)}	V _{EB0}	h _{FE}	h _{FE}	h _{FE}	h _{FE}	V _{CE(SAT)}	V _{BE(SAT)}	T °C
TEMP. 25°C unless noted											(MAX)
TEST EQUIPMENT NO.											
CONDITIONS	I _C = 1mA	I _C = 100mA	I _C = 5A	I _C = 10mA	I _C = 0.5A	I _C = 1A	I _C = 3A	I _C = 5A	I _C = 50mA	I _C = 1.0A	I _C = 5A
					V _{CE} = 5V	V _{CE} = 5V	V _{CE} = 5V	V _{CE} = 5V	I _R = 0.5A	I _R = 0.1A	V _{CE0(SUS)}
											290V
LIMITS			90						1.0		
UNITS OF MEASURE									Volt	Volt	
NO. DATE CODE											
1	132	88	110	7	275	275	275	170	0.21	0.79	260
2	118	89	100	7	260	275	275	150	0.24	0.80	260
3	108	90	90	6.9	200	225	240	173	0.21	0.79	250
4	124	93	100	6.8	210	230	250	135	0.24	0.79	260
5	118	89	98	6.9	285	290	290	150	0.20	0.79	250
6	130	87	98	7	275	275	280	188	0.21	0.79	255
7	128	88	100	7	275	275	280	160	0.22	0.79	250
8	120	92	98	6.7	240	250	250	140	0.21	0.79	255
9	118	90	98	6.8	240	250	250	135	0.22	0.79	255
10	132	88	100	7	275	280	280	175	0.20	0.79	260
11	128	87	98	6.8	285	280	280	175	0.21	0.79	250
12	116	90	98	6.9	240	240	240	150	0.23	0.79	260
13	128	87	100	7	260	260	250	155	0.21	0.79	250
14	128	88	100	7	275	280	282	163	0.21	0.79	260
15	132	87	100	7	290	290	290	180	0.21	0.79	255
16	112	86	98	7	275	280	285	175	0.21	0.79	255
17	124	89	100	6.5	260	260	260	155	0.23	0.80	255
18	112	94	98	6.6	205	225	240	125	0.22	0.79	250
19	128	88	100	7	250	260	255	165	0.21	0.79	250
20	124	94	103	6.7	163	188	210	112	0.25	0.80	250

RELIABILITY ☐ PAGE 2 OF 2
PRE-SHIP INSP. ☐
FINAL INSP. ☐ DATE 8-19-70

[illegible]

PUSH
TO
TEST

$t_p = 10 \mu s$
 $f = 0.01 Kc$
H/p 214A

V_3
6V

$V_1 +$
30V

$V_1 -$

ADJ. TO $I_c = 100 A$

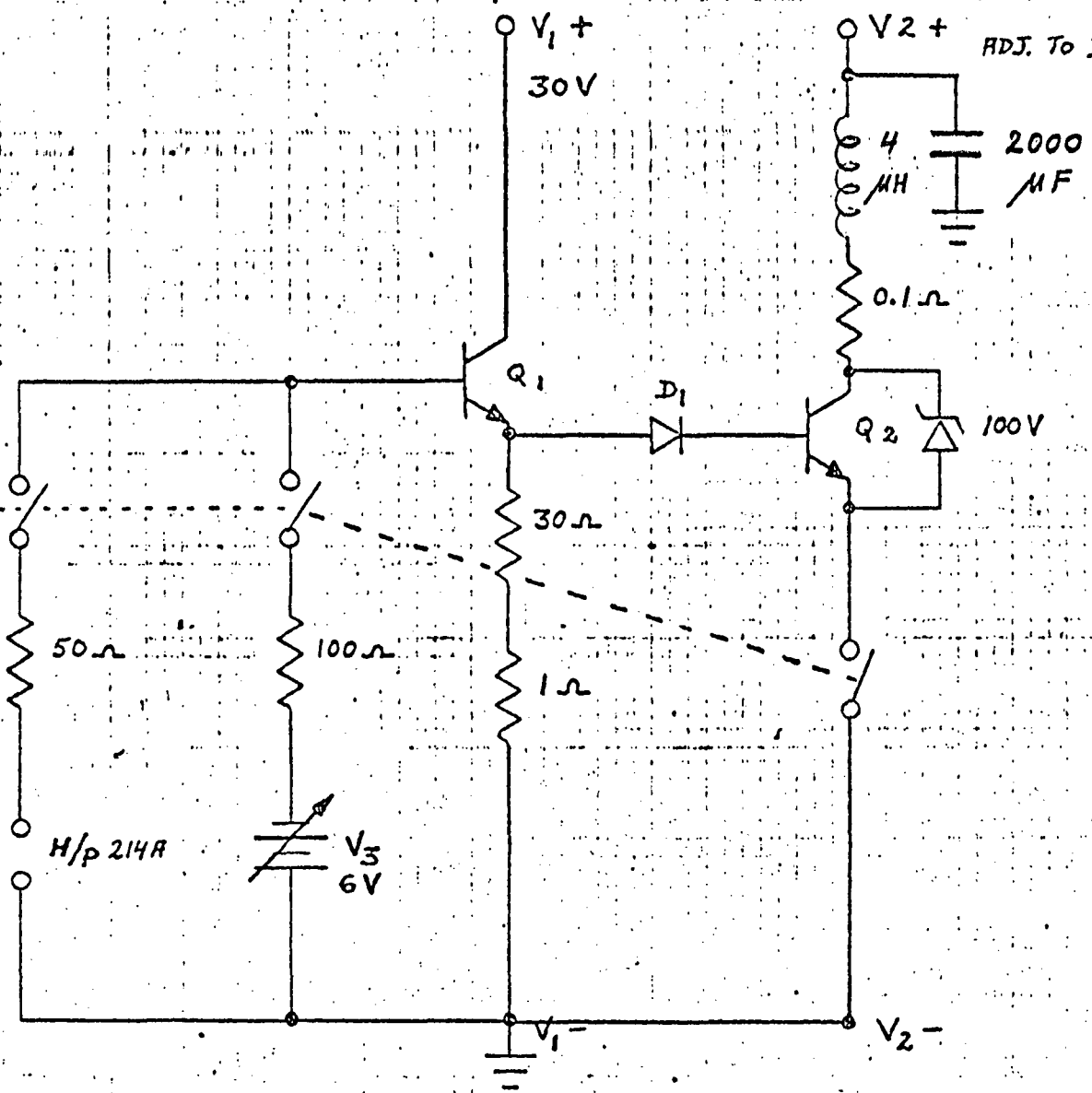
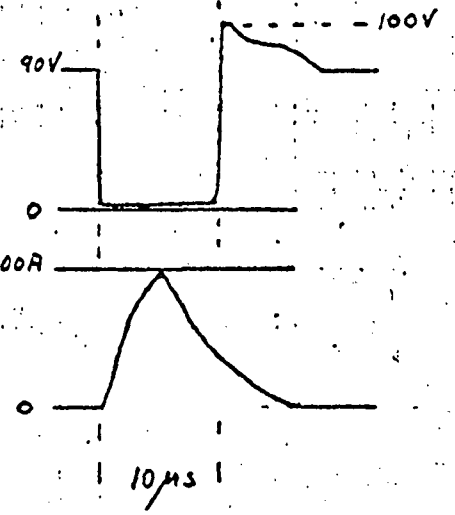
$V_2 +$

0.1 Ω

Q_2

100V

$V_2 -$



TEST DATA SHEET

RELIABILITY O PAGE 1 OF 1

PRE-SHIP LSP. C

FINAL MSR. 0 DATE _____

[illegible]

RELIABILITY ☐ PAGE 1 OF 1

PRE-SHIP INSP. ☐

FINAL INSP. ☐ DATE _____

[illegible]

TEST DATA SHEET

RELIABILITY ☒ PAGE OF

PRE-SHIP INER. ①

FINAL INSP. 0 DATE

[illegible]

SOLITRON SERVICES, INC.
1177 BLUE HORIZON BLVD.
RIVIERA BEACH, FLA. 33404
PHONE (305) 848-3411

TEST DATA SHEET

TYPE 3R5M (DUAL) LOT NO. 3R-7D LOT SIZE _____ SAMPLE SIZE _____

RELIABILITY ☐ PAGE _____ OF _____

CUSTOMER NASA CUSTOMER P. O. _____ TESTER _____

PRE-SHIP INSP. ☐ DATE _____
FINAL INSP. ☐ _____

[illegible]

TEST DATA SHEET

RELIABILITY ☐ PAGE 1 OF 1

PRE-SHIP INSP. ☐

FINAL INSP. 0 DATE 11-11-68

[illegible]

A new sample was fabricated and the devices were tested with essentially the same results. This sample showed very little difference in the voltages of the two types of construction. At this time it was decided that reducing the duty cycle might increase the high temperature capability. Therefore, the devices were re-tested at a 10% duty cycle instead of the 50% duty cycle which had been used previously. This resulted in transistor operation at 300°C. In addition samples from lot 3R-6 were retested with the same result. The temperature was not raised above 300°C due to the limitation of the equipment.

In view of the above results a lot of forty devices of dual chip construction in the T0-61 non-isolated package was fabricated. The delivery of twenty of these units was made on 6-3-71 to satisfy the requirements of exhibit A, para. B2b of the contract.

RELIABILITY ☐ PAGE OF

PRE-SHIP INSP. ☐

FINAL INSP. ☐ DATE _____

FINAL INSP. ☐ DATE _____

[illegible]

TYPE GRSM LOT NO. FINAL LOT SIZE _____ SAMPLE SIZE 10-41 RELIABILITY ☐ PAGE 1 OF 2
CUSTOMER NAS 8-25917 CUSTOMER P.O. _____ TESTER _____ PRE-SHIP INSP. ☐
FINAL INSP. ☐ DATE _____

PARAMETER		BV _{CB0}	BV _{EB0}	BV _{CE0}	IC _{B0}	IE _{B0}	ICE ₀	HFE	HFE	HFE	HFE	HFE	
TEMP. 25°C unless noted													
TEST EQUIPMENT NO.													
CONDITIONS		1MA	1MA	50MA	90V	3V	90V	0.5A	1A	3A	5A	7A	
								5V	5V	5V	5V	5V	
LIMITS													
MIN. MAX.													
UNITS OF MEASURE													
NO.	DATE CODE	V	V	V									
1		116	6.2	90	16 nA	6 nA	54 uA	175	190	195	170	115	
2		116	6.2	84	145 nA	6 nA	520 uA	210	210	220	200	195	
3		110	6.1	84	360 nA	42 nA	215 uA	210	215	225	225	210	
4		116	6.3	89	5.4 uA	33 nA	130 uA	160	170	180	175	175	
5		114	6.2	83	58 nA	420 nA	260 uA	220	260	265	240	220	
6		128	6.1	112	8 uA	650 nA	13 uA	175	180	190	180	155	
7		110	6.1	83	23 uA	8.2 nA	21 ^{MA} 21	260	270	280	260	260	
8		116	6.4	95	7.4 uA	1.2 nA	155 uA	175	190	195	180	170	
9		114	6.4	90	1.6 uA	5.9 nA	90 uA	180	190	200	190	190	
10		112	6.3	85	125 nA	32 nA	2 MA	260	280	280	260	220	
11		110	6.1	87	510 nA	45 nA	175 uA	175	180	180	175	170	
12		126	6.3	106	1.4 uA	200 nA	79 uA	195	200	200	190	170	
13		116	6.2	85	195 nA	8 nA	145 uA	200	220	220	200	200	
14		122	6.1	104	23 nA	79 nA	18 uA	180	180	190	180	160	
15		112	6.2	86	92 nA	14 nA	530 uA	220	260	260	240	240	
16		110	6.3	88	26 uA	215 uA	36 uA	195	200	210	200	200	
17		108	6.1	88	42 nA	320 nA	2.6 uA	195	200	210	195	195	
18		112	5.8	83	15 nA	66 nA	16 uA	230	250	265	260	260	
19		118	6.2	87	2.7 uA	18 nA	51 uA	210	220	240	230	210	
20		112	6.2	87	9.4 nA	17 nA	2.3 uA	180	190	195	180	180	

TYPE 6R5M LOT NO. FINAL LOT SIZE _____ SAMPLE SIZE T0-61 RELIABILITY ☐ PAGE 2 OF 2
CUSTOMER NAS 8-25917 CUSTOMER P. O. _____ TESTER _____ PRE-SHIP INSP. ☐
FINAL INSP. ☐ DATE _____

PARAMETER	$V_{CE(SAT)}$	$V_{BE(SAT)}$	C_{OBO}	C_{iBO}	$V_{CE0(SOS)}$	T_{oc}	T_{oc}						
TEMP. 25°C unless noted													
TEST EQUIPMENT NO.													
CONDITIONS	<u>5A</u>	<u>5A</u>	<u>10V</u>	<u>3V</u>	<u>5A</u>	<u>5A</u>	<u>5A</u>						
	<u>0.5A</u>	<u>0.5A</u>	<u>1MHZ</u>	<u>1MHZ</u>		<u>>90V</u>	<u>>90V</u>						
						<u>50% D.C.</u>	<u>10% D.C.</u>						
UNITS													
MIN													
MAX													
UNITS OF MEASURE													
NO.													
DATE CODE													
	<u>V</u>	<u>V</u>	<u>PF</u>	<u>PF</u>		<u>°C</u>	<u>°C</u>						
1	0.24	0.96	180	1300	90V	280	300						
2	0.19	0.92	180	1400	90V	280	300						
3	0.16	0.87	180	1400	90V	285	300						
4	0.19	0.90	185	1400	90V	275	300						
5	0.18	0.90	185	1400	90V	280	300						
6	0.17	0.88	160	1450	110V	290	300						
7	0.16	0.88	180	1400	120V	280	300						
8	0.16	0.87	170	1450	90V	285	300						
9	0.18	0.90	180	1400	90V	290	300						
10	0.19	0.92	180	1350	95V	290	300						
11	0.19	0.91	185	1400	100V	295	300						
12	0.17	0.88	165	1450	90V	285	300						
13	0.18	0.89	185	1400	90V	290	300						
14	0.18	0.90	165	1500	95V	290	300						
15	0.16	0.87	180	1400	90V	290	300						
16	0.18	0.88	185	1400	90V	280	300						
17	0.16	0.88	180	1450	90V	290	300						
18	0.17	0.89	185	1350	100V	280	300						
19	0.20	0.95	185	1350	90V	285	300						
20	0.18	0.89	185	1400	100V	280	300						

SPEEDY SET MODEL BUSINESS FORMS INC., FT. LAUDERDALE, FLA.

Soliton DEVICES, INC.
TRANSISTOR DIVISION

AC - PHONE
305 - 848-4311

ORIGINAL

INVOICE

77 BLUE HERON BLVD., RIVIERA BEACH, FLORIDA 33404

VOICE TO
• NASA
George C. Marshall Space Flight Center
Marshall Space Flight Center
• Alabama 35812

SHIP TO
Same
Accountable Property Officer
Bldg. 4471

TERMS - 1/2% 10, NET 30 DAYS
F.O.B. RIVIERA BEACH, FLORIDA
DATE PROMISED

ORDER NUMBER	CUSTOMER ORDER NUMBER	SHIPPED VIA	REPRESENTATIVE	INVOICE DATE	DATE PROMISED
		Hand Carried - R. Howard	6/2/71		
20	20	NASA Contract NA 58-25917 DCN 1 - 0 - 40 - 02692, & S1 Medium Power Transistors with read and record data (Exhibit A, Para. B 2b)			

WE CERTIFY THAT THESE GOODS WERE PRODUCED IN COMPLIANCE WITH ALL APPLICABLE REQUIREMENTS OF SECTIONS 6, 7 AND 12 OF THE FAIR LABOR STANDARDS ACT, AS AMENDED, AND OF REGULATIONS AND ORDERS THEREUNDER. THESE GOODS WERE PRODUCED IN THE UNITED STATES OF AMERICA. IF EXPORTED, THESE GOODS WILL BE EXPORTED IN COMPLIANCE WITH THE EXPORT ADMINISTRATION ACT, AS AMENDED, AND OF REGULATIONS AND ORDERS THEREUNDER. THESE GOODS WERE PRODUCED IN THE UNITED STATES OF AMERICA. IF EXPORTED, THESE GOODS WILL BE EXPORTED IN COMPLIANCE WITH THE EXPORT ADMINISTRATION ACT, AS AMENDED, AND OF REGULATIONS AND ORDERS THEREUNDER.

No. T 58732

C. 10 Ampere Rectifier.

A planar rectifier was designed for this project to provide a device capable of assembly with a hard eutectic mount and aluminum wire bonding. This device was designed for a 30 amp capability under normal operating conditions to insure the device operation at high temperature.

The first two diffusion runs yielded devices which would meet the reverse voltage characteristics but were too high in forward voltage characteristics. This problem was solved by diffusing an N+ layer into the back of the slice.

Twenty-five devices were assembled in DO-5 packages and tested at 300°C. The reverse leakage at 200V V_R and 300°C ranged between 11 MA and 25 MA. Twenty of these devices were delivered to NASA-MSFC on 7-12-71 to satisfy the requirements of exhibit A, para. B.2C of the contract.

of

DATE _____

[illegible]

Soliton DEVICES, INC.
TRANSISTOR DIVISION

 1177 BLUE HERON BLVD., RIVIERA BEACH, FLORIDA 33404
 POSTMASTER - CONTENTS MERCHANDISE - RETURN REQUESTED

Soliton DEVICES, INC.
TRANSISTOR DIVISION

 1177 BLUE HERON BLVD., RIVIERA BEACH, FLORIDA 33404
 POSTMASTER - CONTENTS MERCHANDISE - RETURN REQUESTED

 NASA
 GEO. C. MARSHALL SPACE FLT. CENTER
 MARSHALL SPACE FLIGHT CENTER
 ALABAMA 35812

 SAME
 ACCOUNTABLE PROPERTY OFFICER
 BLDG. 4471

 CUSTOMER'S
 ORDER NO.

 CUSTOMER'S
 ORDER NO.

ORDER NUMBER	CUSTOMER ORDER NUMBER	SHIPPED VIA	REPRESENTATIVE	INVOICE DATE	DATE PROMISED
		UPS		7/13/71	
20		20	NAS8-25917 DCN 1-0-40-02692, & S1 MEDIUM POWER TRANSISTORS WITH READ AND DATA (EXHIBIT A, PARA. B 2C)		
PACKING LIST					

 SOLITRON DEVICES, INC. TRANSISTOR
 DIVISION

1177 BLUE HERON BLVD., RIVIERA BEACH, FLORIDA 33404

No. T 50796

IV. DISCUSSION

For a semiconductor device, whether it be a rectifier or a transistor, it is usual practice to base the maximum power rating on the theoretical allowable temperature the junction can attain. For silicon this is about 250°C. Beyond this temperature, the conduction becomes predominantly intrinsic, and the junction loses its rectification properties.

This is illustrated on a graph of resistivity versus temperature, for N-type silicon. This graph was reproduced in part from current literature. The 10^{15} doping curve is the nearest illustrated one to the doping level required to fabricate the six to eight ohm-cm material needed to sustain a 90 volt BV_{ceo} . The curves for the required material would fall between the 10^{14} and the 10^{15} curves but closer to the 10^{15} curve.

It can be seen that the 10^{15} curve peaks in resistivity at about 210°C. It becomes more conductive from this point until it meets the intrinsic curve at about 295°C. It is at the peak of the curve that the mobile carriers created by thermal ionization of the intrinsic semiconductor begin to outnumber the impurity-donated carriers and this continues until the semiconductor becomes completely intrinsic. The curves for the required material meet the intrinsic curve at lower temperatures than the 10^{15} curve.

This is the main problem encountered in attempting to fabricate a 300°C operating silicon device. Marginally successful operation was attained with the five ampere transistor and the power rectifier because these devices were made much larger than necessary for normal operation to allow for the increased power dissipation. The five ampere device would be normally rated as a twenty ampere device and the 10 ampere device would normally be a thirty ampere device.

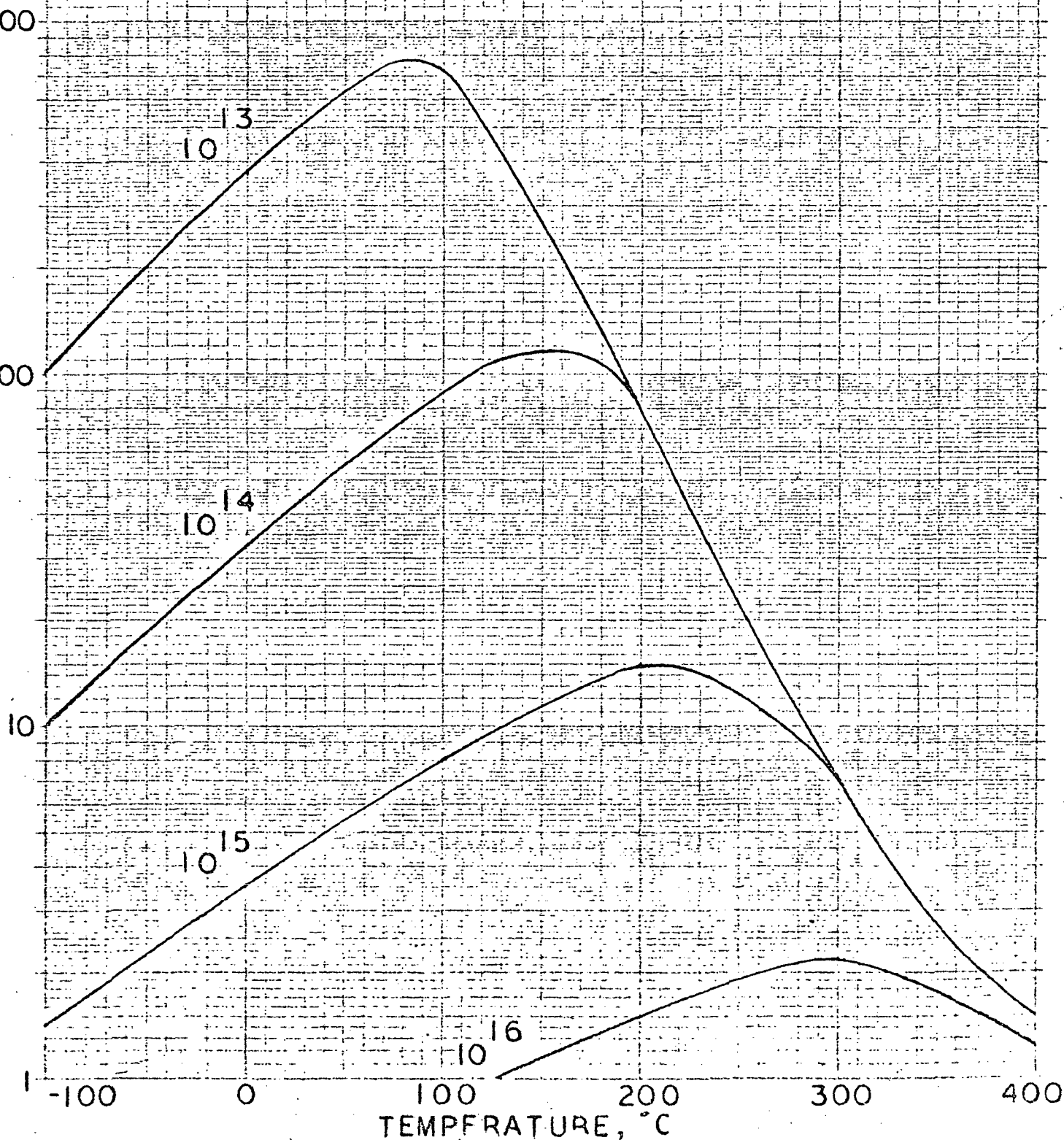
The problem was greatly increased in attempting to fabricate a 100 ampere device to operate at 300°C. Experiments indicated that paralleling the devices was a reasonable approach up to a certain point for temperature up to 200°C. When attempting to increase the power dissipation, it was found that problems in oscillations occurred. The oscillation was probably due to the increase in wiring

RESISTIVITY VS TEMPERATURE FOR N-TYPE SILICON

SEMILOGARITHM
FOUR 250 CYCLES X 50 DIVISIONS
SHEET 01, 117, ENGRAVING 7 A10

RESISTIVITY OHM-CM

GRILVIE PRESS, INC.
BROOKLYN 17, NEW YORK
MANUFACTURED IN U.S.A.



necessary to connect the chips and possibly a mis-match of gain at high currents. Since gain can only be measured at low current (500 ma) in chip form, it is difficult to predict the match at high current (100 amp) within ten percent. A mis-match could cause one chip to pass more current than another chip leading to destruction. This coupled with thermal stress on the breakdown characteristics of the device leading to secondary breakdown virtually makes it impossible to fabricate the device.

The problem is further complicated by the radiation hardness specifications of the device. This limits the starting resistivity, the epitaxial thickness, diffusion depths, base width, and the physical size of the device that will support the shallow diffusions.

In view of the complications encountered, it is felt that functional reliable devices fabricated from silicon can not be expected to operate at 300°C and that radiation resistance may be enhanced if the voltage requirement could be lowered so that lower resistivity material be utilized.

V.

ENGINEERING DEVICE SPECIFICATIONS

ENGINEERING DEVICE SPECIFICATION

DOUBLE DIFFUSED EPITAXIAL
RADIATION HARDENED DEVICEPROCESS FLOWS. O. D.

1. Receive Slices	602111-1
2. Run Make Up and Clean Slices	669
3. Oxidize Slice	301
4. Base Photo Resist	
a) Coat & Bake	356
b) Mask & Expose	633
c) Develop	634
d) Inspect & Bake	350
e) Etch	358
5. Boron Deposition	660
6. Boron Deposition	670
7. Remove Boron Glass	304
8. Boron Diffusion--(Base)	671
9. Emitter Photo Resist	
a) Coat & Bake	356
b) Mask & Expose	633
c) Develop	634
d) Inspect & Bake	350
e) Etch	358
10. Phosphorous Deposition Clean	660
11. Phosphorous Deposition & Diffusion (Emitter)	672

SOLITRON

RIVIERA BEACH, FLORIDA

FOR DOUBLE DIFFUSED EPITAXIAL
RADIATION HARDENED DEVICE

DATE 8-1-72 DRWN. KW

CHKD. *BA*APPD. *KW*

NO.

Page 1 of 4

REVISION

DATE E.O.

PROCESS FLOWS.O.D.

12.	Low Temperature Oxide	673
13.	Contact Photo Resist	
a)	Coat & Bake	356
b)	Mask & Expose	633
c)	Develop	634
d)	Inspect & Bake	350
e)	Etch	358
14.	Evaporation Clean	660
15.	Aluminum Evaporation	355
16.	Aluminum Removal Photo Resist	
a)	Coat & Bake	356
b)	Mask & Expose	633
c)	Develop	634
d)	Inspect & Bake	350
e)	Etch and Photo Resist Removal	653
17.	Sinter Aluminum Contacts	311
18.	300°C Vacuum Bake (Wafer)	662
19.	Wafer Scribe	333
20.	Dice Separation	313
21.	Clean Dice	331
22.	Test Dice Electrical	674
23.	Visual Die Inspect	314
24.	Clean Header	222

SOLITRON

RIVIERA BEACH, FLORIDA

FOR DOUBLE DIFFUSED EPITAXIAL
RADIATION HARDENED DEVICE

DATE 8-7-72 DRWN. KW

CHKD. *gpl*APPD. *gpl*

NO.

2 of 4

REVISION

DATE E.O.

PROCESS FLOWS. O. D.

25. Mount Die	260
26. Ultrasonic Lead Attach (die)	257
27. Lead Attach (Post)	258
28. Clean Assembly	259
29. Visual Inspection	276
30. Clean Cap	222
31. Vacuum Bake Assembly & Caps	240
32. Encapsulate	262
33. Fine Leak	261 or 561
34. Heat Age	330
35. Thermo Shock	555
36. Bubble Test	559
37. Electrical Test	

SOLITRON

RIVIERA BEACH, FLORIDA

FOR DOUBLE DIFFUSED EPITAXIAL
RADIATION HARDENED DEVICE

DATE 8-7-72 DRWN. KW

CHKD. *Red*APPD. *T.M.M.*

NO.

3 of 4

REVISION

DATE E.O.

TABLE OF PACKAGE TYPES

<u>TYPE</u>	<u>BASE PART NO.</u>	<u>CAP PART NO.</u>
(TO-61)	600941	600561
100 AMP	IT-A-525	IT-A-523
DIODE	TD-4587	TD-4591

SOLITRON
RIVIERA BEACH, FLORIDA

FOR

DOUBLE DIFFUSED EPITAXIAL
RADIATION HARDENED DEVICE

DATE 8-7-72 DRWN. KW

CHKD. *ALL*

APPD. *T.M.*

NO. 4 of 4

REVISION

DATE E.O.

PARAMETERSDOUBLE DIFFUSED EPITAXIAL RADIATION HARDENED DEVICE

<u>PROCESS PARAMETER</u>	<u>EPITAXIAL</u>
Material Drawing Number	602111-1
Starting Resistivity	$7 \pm 1 \Omega\text{-cm}$
Epitaxial Thickness	$25 \pm 4 \mu$
Boron Deposition Temperature	$940 \pm 20^\circ\text{C}$
Boron Deposition V/I	$13 \pm 1 \sim$
Flow Rates N_2	2.5 L/MIN
O_2	85 CC/MIN
B_2H_6	475 CC/MIN
Boron Diffusion Time. DRY	25 MIN
Boron Diffusion Temperature DRY	1125°C
Flow Rate O_2	1L/MIN
Boron Diffusion Time WET	35 MIN
Boron Diffusion Temperature WET	1125°C
Water Temperature	95°C
Anneal Time to Temperature	60 MIN to 800°C
Base Depth X_j	$7 \pm 1f$
Emitter Deposition Temperature	1050°C
Emitter Deposition Time	3 MIN
Emitter Diffusion Time	13 MIN
Flow Rates N_2	900 CC/MIN
O_2	900 CC/MIN
PO CL_3	620 CC/MIN
Emitter V/I	$1.3 \pm .2 \sim$
Base Width	$3 \pm .5f$
Aluminum Thickness	$20 \pm 5 \text{ KA}^\circ$

REV	REVISION RECORD	DATE	E.O.
B	REDRAWN & REVISED	4-4-72	F-1603

DRAWING NUMBER	REV
602111	B

RESISTIVITY	VOLT. BRK/DN	PART NO.
$8\Omega\text{CM} \pm 20\%$	170 - 200	-1
$5\Omega\text{CM} \pm 20\%$	150 - 170	-2

SUBSTRATE - SEE DRAWING 602298-1 REV. A

EXCEPT NOTE 5, DISLOCATION DENSITY LESS THAN 500 PER CM^2

EPITAXIAL LAYER:

1. EPITAXIAL LAYER - TYPE N (PHOSPHORUS DOPED) SEE TABLE.
2. LAYER THICKNESS - $25 \pm 4 \mu$. MEASURED BY IR METHOD IN 4 MICRON GROUPS OR INDIVIDUALLY MARKED.
3. STACKING FAULTS - 100 CM^{-2} MAXIMUM.
4. SURFACE - FREE FROM VISUAL DEFECTS IF POLISHED.
5. LESS THAN SIX (6) SURFACE DEFECTS IF NOT SURFACE POLISHED.
6. NO SURFACE SPIKES HIGHER THAN TWO (2) MICRONS.
7. BACK LAPPED TO 12 MICRONS FINISH IF EPITAXIAL BUILD UP ON BACK EDGE OF SLICE IS GREATER THAN 12 MICRONS.
8. NO INVERSION.

NOTE: VISUAL DEFECT AND STACKING FAULT COUNTS ARE NOT TO BE CHECKED WITHIN $1/8$ " OF OUTER EDGE, EXCEPT FOR EDGE CROWN.

NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 4-4-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (.01) $\pm .020$ TWO PLACE (.001) $\pm .010$ THREE PLACE (.0001) $\pm .005$	N/N+ 1 1/2" EPITAXIAL WAFER	DRAFTING	LMS 4-4-72	
	FRACTIONAL \pm		ENGINEER		
	ANGULAR \pm		APPROVED	R7/B 4-24-72	
MATERIAL SILICON	SPE SPEC.	SCALE	FULL SIZE		
		DEVICE	NPN		DRAWING NUMBER 602111
					REV B

ENGINEERING DEVICE SPECIFICATION
ZE, 30 AMPERE POWER DIODE (SILICON PLANAR)

PROCESS FLOW

STANDARD OPERATION DETAIL

- | | |
|----------------------------|-------------------|
| 1. Recieve Slices | 600938-1 |
| 2. Clean | 300 or 546 |
| 3. Oxidize Slice | 286 |
| 4. Base Photo Resist | |
| a) Coat & Bake | 214, 413, and 290 |
| b) Mask & Expose | 343 |
| c) Develop | 634 |
| d) Inspect & Bake | 350 |
| e) Remove Oxide | 358 |
| 5. Clean | 550 or 660 |
| 6. Boron Deposition | 282 |
| 7. Reflux | 304 |
| 8. Boron Diffusion | 287 |
| 9. Etch Photo Resist | |
| a) Coat & Bake | 214, 413, and 290 |
| b) Expose | 343 |
| c) Develop | 634 |
| d) Bake | 350 |
| e) Remove Oxide | 358 |
| 10. Clean | 550 or 660 |
| 11. Phosphorous Deposition | 672 |
| 12. Contact Photo Resist | |

SOLITRON

RIVIERA BEACH, FLORIDA

FOR

ZE, 30 AMPERE POWER DIODE (SILICON PLANAR)

DATE 8-8-72 DRW/NKW

CHKD. *[Signature]*

APPD. *[Signature]*

NO. 1 of 4

REVISION

DATE E. O.

PROCESS FLOWSTANDARD OPERATION DETAIL

a) Coat & Bake	214, 413, and 290
b) Mask & Expose	343
c) Develop	634
d) Bake	350
e) Remove Oxide	358
13. Aluminum Evaporation Clean	660 or 550
14. Aluminum Evaporation	309, 355, or 696
15. Metal Etch Photo Resist	
a) Coat & Bake	214, 413, and 290
b) Mask & Expose	343
c) Develop	634
d) Inspect & Bake	350
e) Metal Etch	683
16. Sinter Aluminum	311
17. Bake	318
18. Scribe	333
19. Dice Separation	313
20. Load Block	332
21. Electrical Test (TDE)	See TDE Sheet
22. Clean Dice	331
23. Mount Die	260
24. Ultrasonic Lead Attach	257
25. Resistance Weld	258

SOLITRON

RIVIERA BEACH, FLORIDA

FOR

ZE, 30 AMPERE POWER DIODE (SILICON PLANAR)

DATE 8-8-72 DRWN. KW

CHKD.

APPD.

NO. 2 of 4

REVISION

DATE E.

PROCESS FLOW

26. Stamp Assembly
27. Vacuum Bake
28. Encapsulate
29. Crimp Weld
30. Therma Shock
31. Helium Leak Test
32. Heat Age
33. Pressure Bomb (Gross Leak)
34. Classify

STANDARD OPERATION DETAIL

552
240
262
412
555
261 or 561
330
559

				SOLITRON RIVIERA BEACH, FLORIDA	
				FOR ZE, 30 AMPERE POWER DIODE (SILICON PLANAR)	
				DATE 8-8-72	DRWN. KW
				CHKD.	
				APPD.	
				NO. 3 of 4	

REVISION

DATE E. O.

SUBSTRATE		602298-1
EPITAXIAL LAYER THICKNESS		21-29 u 4-6 cm
BASE DEPOSITON TEMP.		860°C
TIME	5' Dwell; 5' Source; 20' Soak	
V/I	60-80	
B ₂ H ₆ - 0.3 L/MIN; O ₂ - 0.3 L/MIN; N ₂ - 2.5 L/MIN		
BASE DIFFUSION TEMP.		1200°C
TIME	0.5 Hr. Wet O ₂ ; 4.5 Hr. Dry O ₂ N ₂	
V/I	400-600	
Flows N ₂ O ₂	1 L/MIN	
Xj	25-35 f	
EMITTER DEPOSITION TEMP.		1060°C
TIME	5' Dwell; 5' Source; 30 Min Soak in O ₂	
V/I		
PCl ₃ - 0.05 L/MIN; N ₂ - 0.4 L/MIN; O ₂ - 0.225 L/MIN		
N+ DEPOSITION TEMP.		
TIME		
V/I		
FINAL DIFFUSION * TEMP.		
TIME		
SLOW COOL		
BASE WIDTH (W _b)		

* SPECIAL PROCESSING CONSIDERATIONS: See Past history for actual Final Diffusion Time.

SLICE PART NO. 600938-1

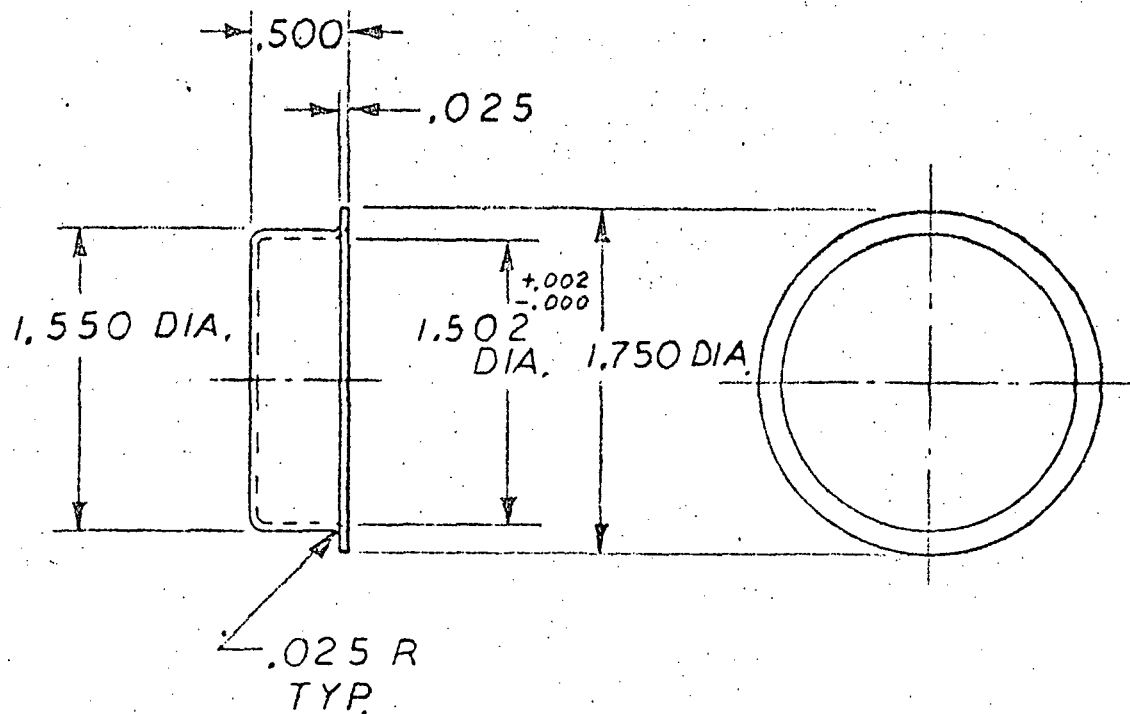
DIE CHARACTERISTICS: BV_{ceo} BV_{ceo} GAIN

PRIME TYPE

VI.

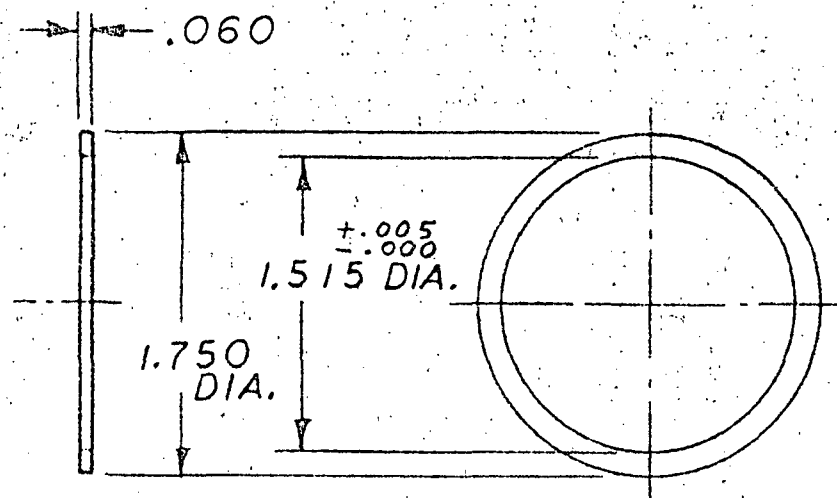
DRAWINGS
(100 AMP)

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				1T-A-523	



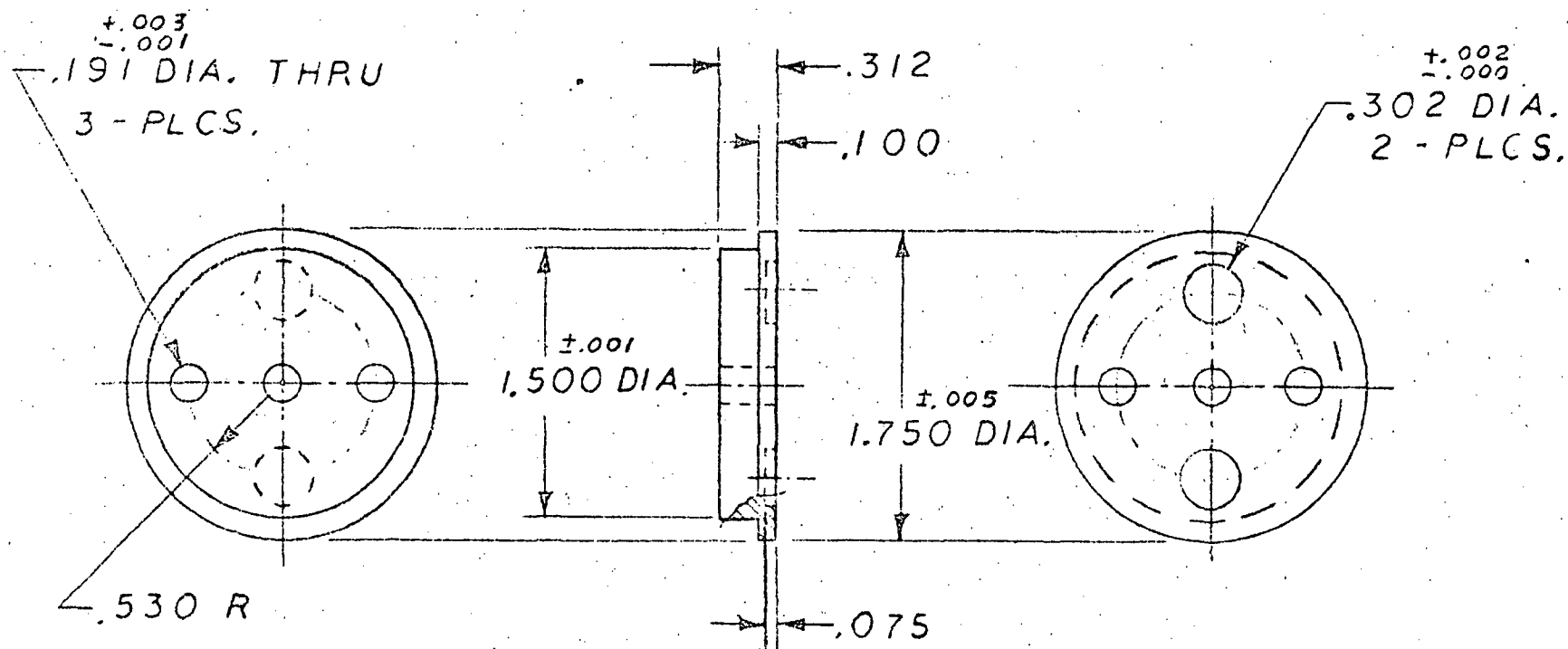
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	ONE PLACE (.0) ±.020 TWO PLACE (.00) ±.010 THREE PLACE (.000) ±.005	CAP	DRAFTING	LMS 6-16-72		
	FRACTIONAL ±		ENGINEER	BR 6-16-72		
	ANGULAR ±		APPROVED	BR 6-16-72		
MATERIAL	STN. STL.	SPE SPEC.	SCALE	FULL SIZE	DRAWING NUMBER	REV
			DEVICE	100 AMP RAD.	1T-A-523	

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				1T-A-524	

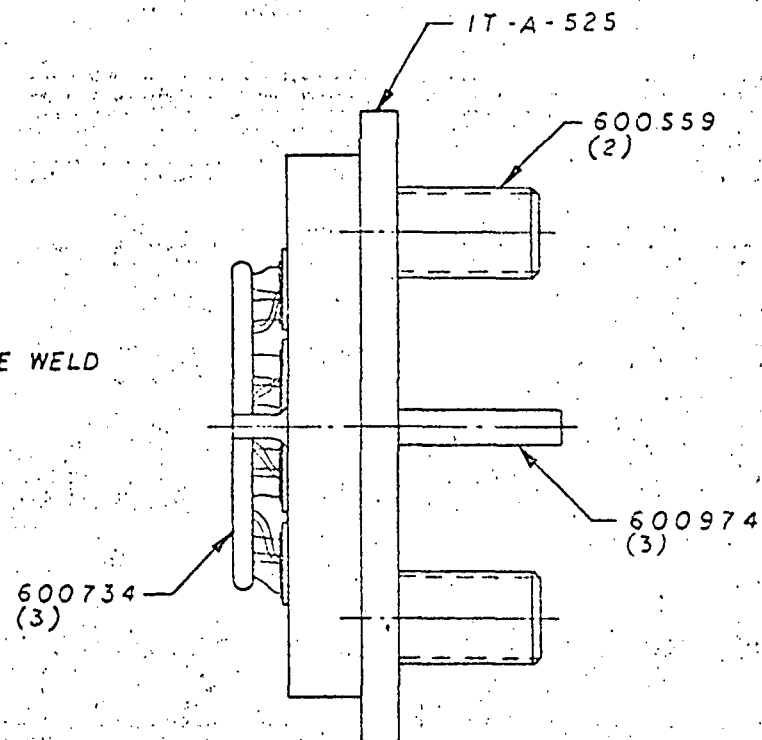
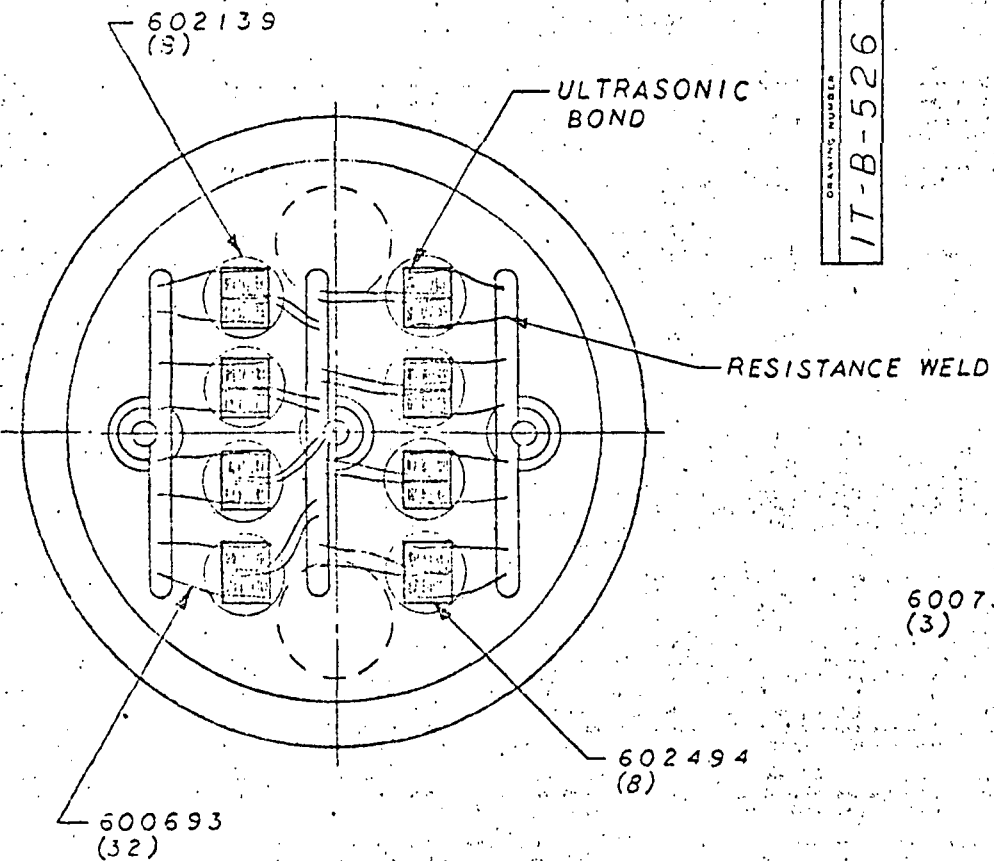


NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 6-16-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (.0) ±.020 TWO PLACE (.00) ±.010 THREE PLACE (.000) ±.005	WELD RING	DRAFTING	LMS 6-16-72	
	FRACTIONAL ±		ENGINEER	BLR 6-16-72	
	ANGULAR ±		APPROVED	BLR 6-16-72	
MATERIAL	CRS	SPE SPEC.	SCALE	FULL SIZE	DRAWING NUMBER
			DEVICE	100 AMP RAD.	1T-A-524

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				1T-A-525	



NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 6-16-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (.01) ±.020 TWO PLACE (.001) ±.010 THREE PLACE (.000) ±.005	BASE	DRAFTING	LMS 6-16-72	
	FRACTIONAL ±		ENGINEER	BCF 6-16-72	
	ANGULAR ±		APPROVED	BCF 6-16-72	
MATERIAL OFHC COPPER		SPE SPEC.	SCALE	FULL SIZE	DRAWING NUMBER
			DEVICE	100 AMP RAD.	1T-A-525



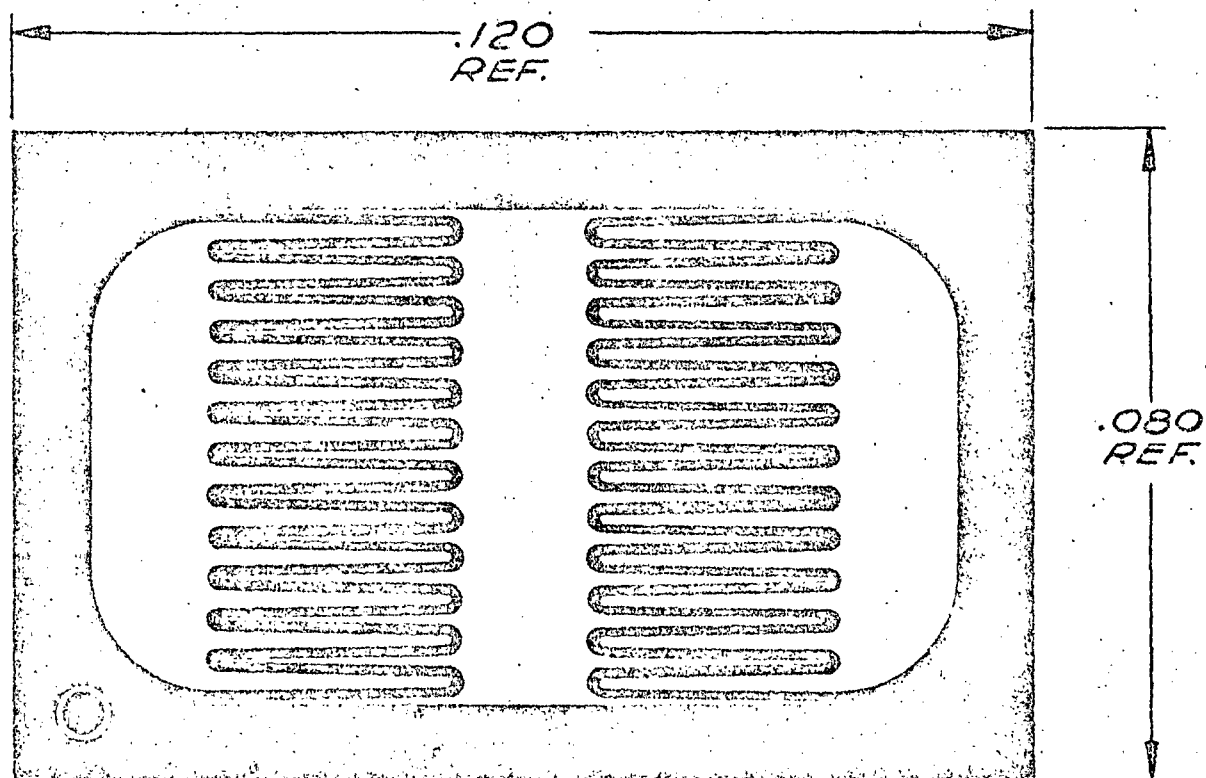
REV	REVISION RECORD	DATE	E. O.	NEAT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 6-17-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
					ONE PLACE ± .01 ± .020	TRANSISTOR & LEAD ASSY	DRAFTING	LMS 6-19-72	
					TWO PLACE ± .001 ± .010		ENGINEER	ZSC 6-20-72	
					FRACTIONAL ±		APPROVED	PC 6-20-72	
					ANGULAR ±				
				MATERIAL	SPE SPEC.	SCALE	3 X SIZE		DRAWING NUMBER
						DEVICE	100 AMP RAD.		1T-B-526

VII.

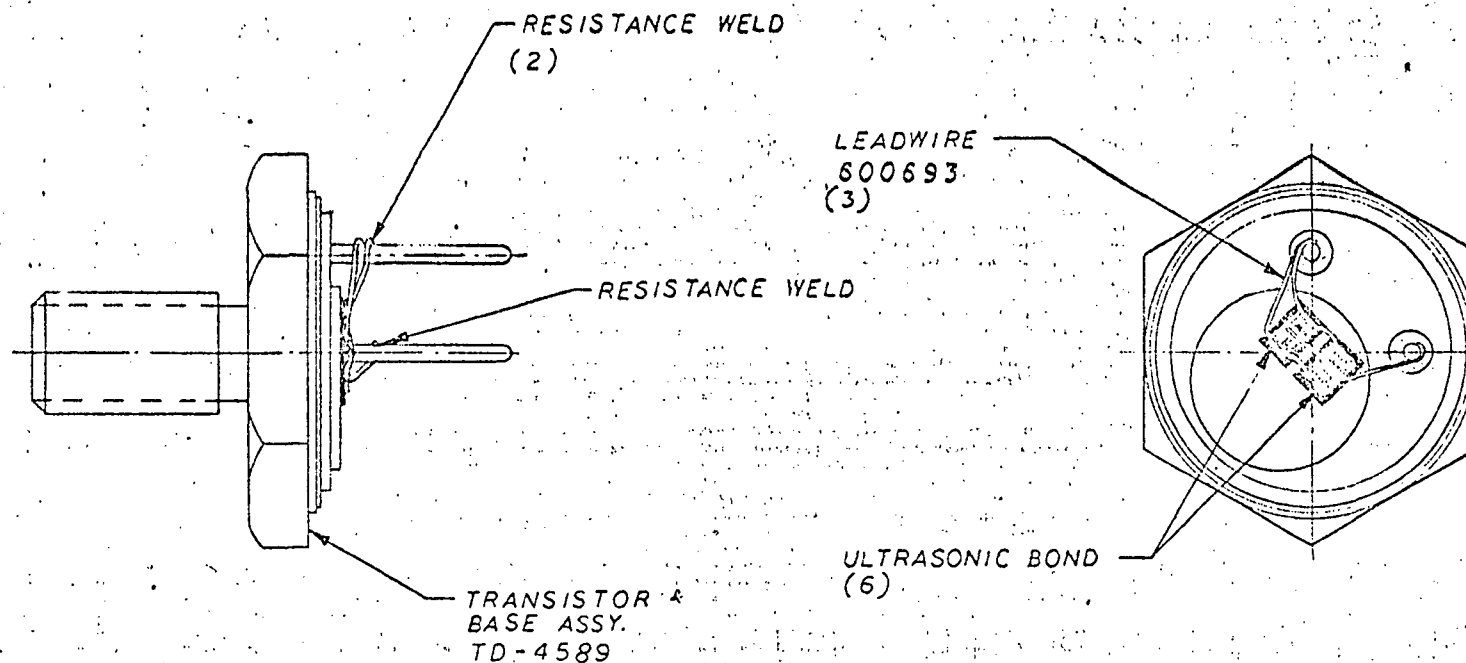
DRAWINGS

5 AMP

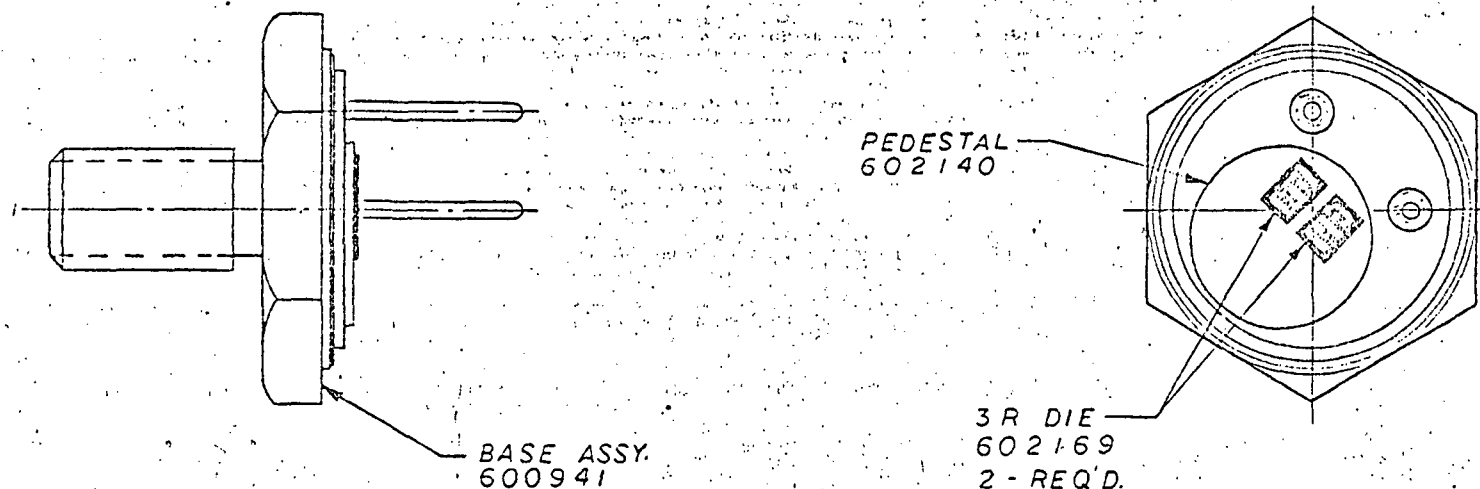
REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				602169	



NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	2-1-71	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (.01) ±.020 TWO PLACE (.001) ±.010 THREE PLACE (.0001) ±.005	COMPOSITE MASK	DRAFTING	RJR 2-1-71	
	FRACTIONAL ±		ENGINEER	2-1-71	
	ANGULAR ±		APPROVED	2-1-71	
MATERIAL		SPE SPEC.	SCALE	42 X	DRAWING NUMBER
			DEVICE	3R DIE	602169



REV		REVISION RECORD	DATE	E. O.	NEXT ASSY ONE PLACE 1.00 TWO PLACE 1.00 THREE PLACE 1.000 FRACTIONAL ANGULAR	TOLERANCE 1.00 1.00 1.000 1.000 1.000	DRAWING TITLE TRANSISTOR & LEAD ASSY.	DRAWN LMS 7-31-72	DRAFTING LMS 7-31-72	ENGINEER JAC 7-31-72	APPROVED SP 8-2-72	SCALE 4 X SIZE 6 RSM	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA	DRAWING NUMBER TD-4590	REV
					MATERIAL			SPE. SPEC.	DEVICE						



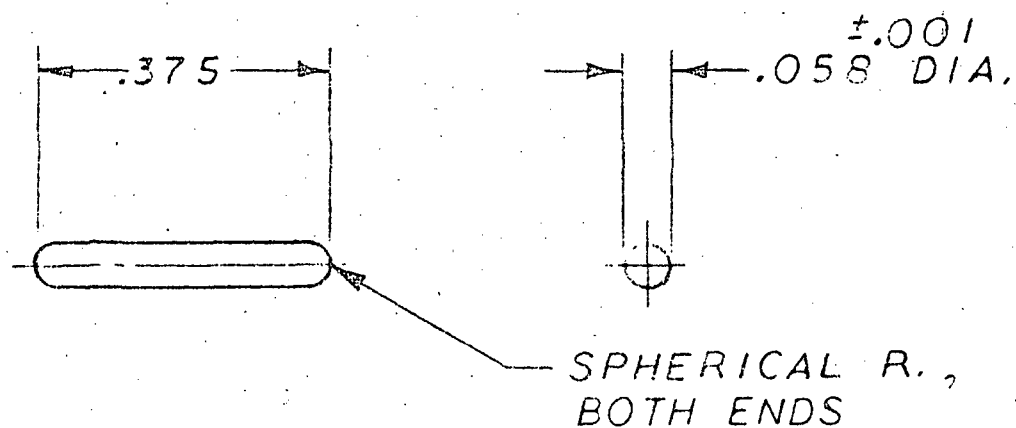
REV
DRAWING NUMBER
TD-4589

REV	REVISION RECORD	DATE	E.O.	NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 7-31-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
				TD-4589	ONE PLACE .001 IN. DIA TWO PLACE .0001 IN. DIA THREE PLACE .0001 IN. DIA	TRANSISTOR & BASE ASSY.	DRAFTING	LMS 7-31-72	
				FRACTIONAL ±	ENGINEER		AC 2-31-72		
				ANGULAR ±	APPROVED		BR 3-2-72		
MATERIAL				SPE SPEC.	SCALE	4 X SIZE		DRAWING NUMBER	REV
					DEVICE	6 RSM		TD-4589	

VIII.

DRAWINGS
RECTIFIERS

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				602506	

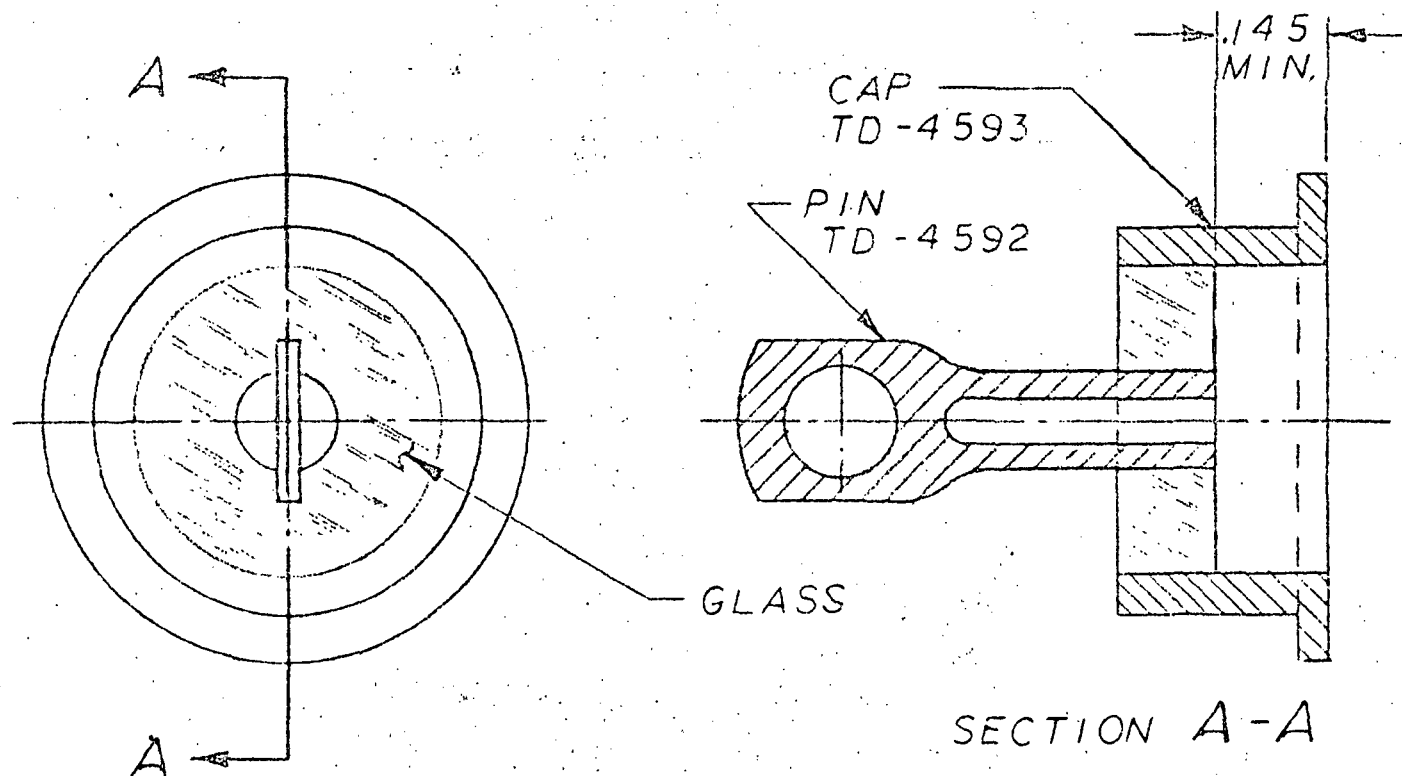


NOTES:

1. MATERIAL: 3:1, 52 ALLOY, COPPER CORE.

NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 7-25-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (0) 2.020 TWO PLACE (00) 2.010 THREE PLACE (000) 2.005	STAND-OFF PIN	DRAFTING	LMS 7-25-72	
	FRACTIONAL 2		ENGINEER	J.R. 8-14-72	
	ANGULAR 2		APPROVED	J.R. 8-14-72	
MATERIAL	SEE NOTE 1	SPE SPEC.	SCALE	4 X SIZE	DRAWING NUMBER
			DEVICE	DO-5	602506

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				TD-4591	



NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LM S 8-11-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
	ONE PLACE (1.0) ±.020	CAP ASSY.	DRAFTING	LM S 8-11-72	
	TWO PLACE (1.00) ±.010		ENGINEER	J.R. 7-11-72	
	THREE PLACE (1.000) ±.005		APPROVED	B.P. 7-11-72	
	FRACTIONAL ±				
	ANGULAR ±				
MATERIAL	SPE SPEC.	SCALE	4 X SIZE	DRAWING NUMBER	REV
		DEVICE	DO-5	TD-4591	

REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				TD - 4591	

1. FINISH: CLEAN WITH NO RESIDUE OR PARTICLES IN TUBES OR ON HEADER.
2. SEALS & TERMINALS MUST WITHSTAND HEATING TO 350°C AFTER WHICH LEAKAGE SHALL NOT EXCEED 1×10^{-9} ATM CC/SEC. RISE TIME 5 MIN. TIME AT TEMP $\frac{1}{2}$ HR. MIN., ROOM AMBIENT COOL.
3. MINIMUM BREAKDOWN VOLTAGE ACROSS GLASS TO BE 500V/60~
4. TERMINAL MUST WITHSTAND 20 LB PULL OR 20 IN. ØZ TORQUE AFTER WHICH LEAKAGE SHALL NOT EXCEED 1×10^{-9} ATM CC/SEC.
5. GLASS TO BE OPAQUE.
6. PART MUST MEET CONDITION OF THERMAL SHOCK, MIL STD 202, METHOD 1107A, TEST CONDITION C-10 CYCLES, AFTER WHICH LEAKAGE SHALL NOT EXCEED 1×10^{-9} ATM CC/SEC.
7. PART MUST MEET CONDITIONS OF THERMAL SHOCK (GLASS STRAIN), MIL STD 750, METHOD 11056 CONDITION A, 30 CYCLES, AFTER WHICH LEAKAGE SHALL NOT EXCEED 1×10^{-9} ATM CC/SEC.
8. EXTERIOR FINISH TO BE 63.
9. MAX LEAKAGE BETWEEN ISOLATED PIN & CASE TO BE 100~A MEASURED BY APPLYING 1100V.

NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 8-11-72	<div style="font-size: 24pt; font-weight: bold;">SOLITRON DEVICES INC.</div> <div style="font-weight: bold;">TRANSISTOR DIVISION</div> <div style="font-weight: bold;">RIVIERA BEACH, FLORIDA</div>
	ONE PLACE (1.0) 1.020 TWO PLACE (1.00) 1.010 THREE PLACE (1.000) 1.005	CAP ASSY.	DRAFTING	LMS 8-11-72	
	FRACTIONAL ±		ENGINEER	BR 8-14-72	
	ANGULAR ±		APPROVED	HP 8-14-72	

MATERIAL	SPE SPEC.	SCALE	4 X SIZE	DRAWING NUMBER	REV
		DEVICE	DO - 5	TD - 4591	

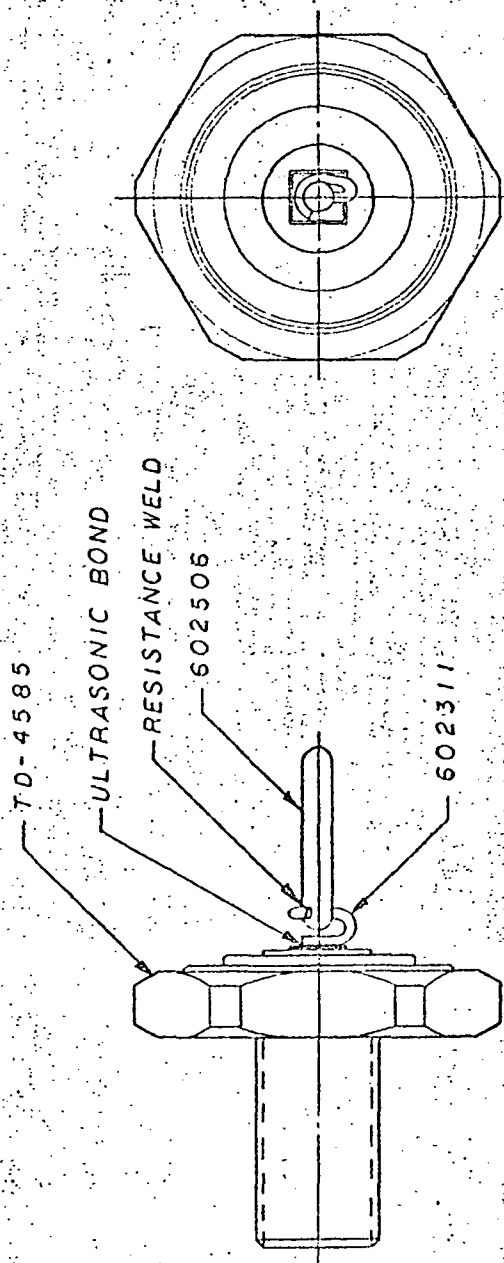
REV	REVISION RECORD	DATE	E.O.	DRAWING NUMBER	REV
				602358	

The drawing shows a central square mask area. The overall width is .120 and the overall height is .120. The mask area itself is .116 wide and .116 high. The border between the mask and the overall frame is .002 wide on all sides.

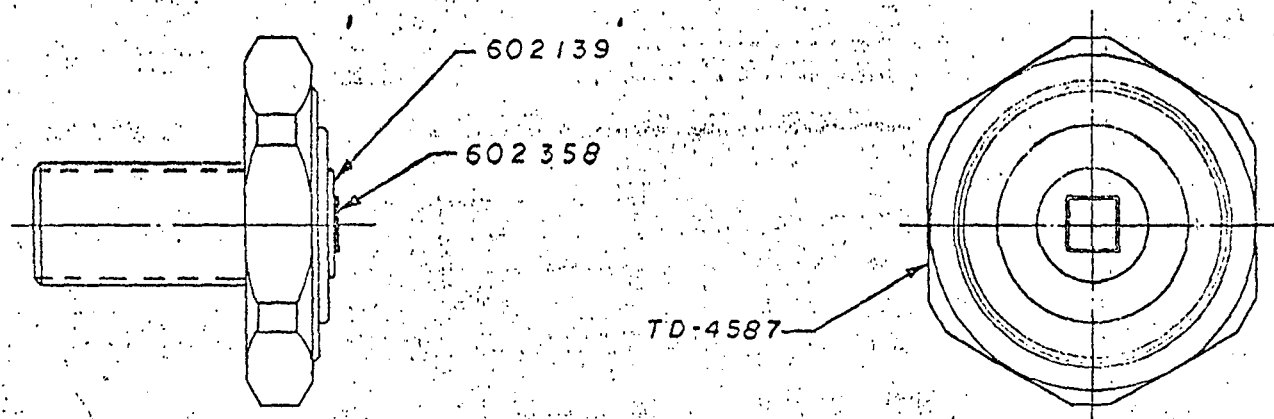
NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	3471	<div style="font-size: 1.2em; font-weight: bold;">SOLITRON DEVICES INC.</div> <div>TRANSISTOR DIVISION</div> <div>RIVIERA BEACH, FLORIDA</div>
	ONE PLACE (1.0) ±.020	<div style="font-size: 1.2em; font-weight: bold;">COMPOSITE MASK</div>	DRAFTING	3471	
	TWO PLACE (1.00) ±.010		ENGINEER		
	THREE PLACE (1.000) ±.005		APPROVED		
	FRACTIONAL ±				
	ANGULAR ±				

MATERIAL	SPE SPEC.	SCALE	30X	DRAWING NUMBER	REV
		DEVICE	ZE DIODE	602358	

12W 419064702112400

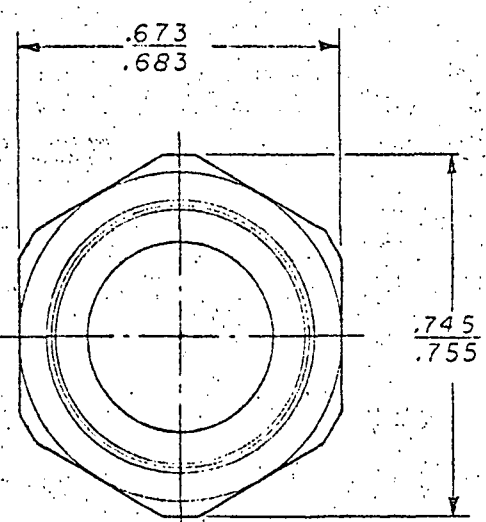
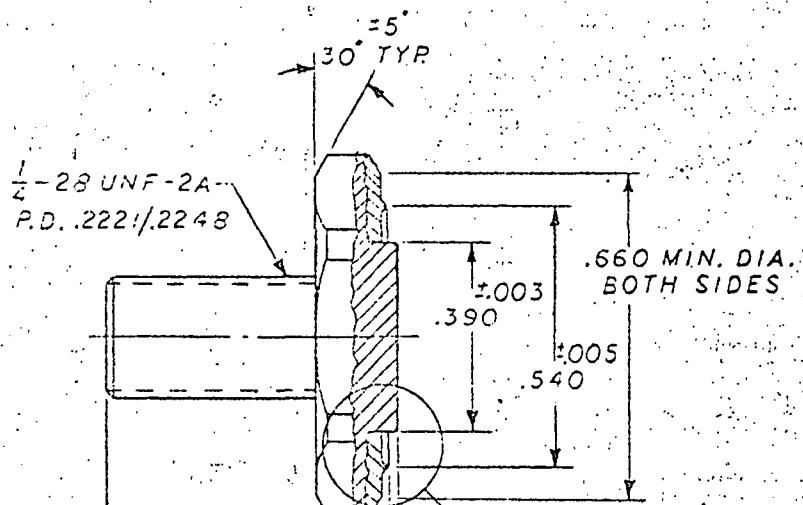


REV	REVISION RECORD	DATE	E. O.					MATERIAL		SPEC.		SCALE		4 X SIZE		DRAWN BY: J. K. JONES		SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA	
												DEVICE		00 - 5		TD - 4586			
								MEET ASSY		TOLERANCE		DRAWING TITLE		DRAWN		LMS 7-25-72			
										ONE PLACE 1.001 1.010		DIODE		DRAFTING		LMS 7-25-72			
										THREE PLACE 1.001 1.010		& LEAD ASSY		ENGINEER		BR 8-14-72			
										FRACTIONAL ±				APPROVED		BR 8-14-72			
										ANGULAR ±									

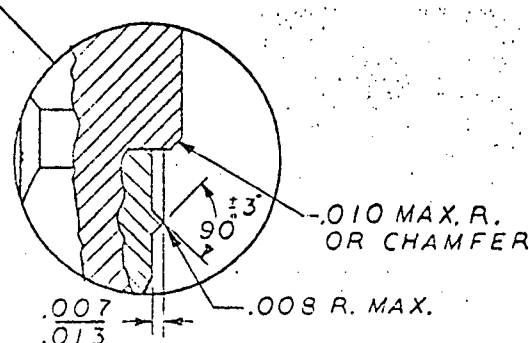


DRAWING NUMBER
REV
TD-4585

REV	REVISION RECORD	DATE	E. O.	NEXT ASSY	TOLERANCE	DRAWING TITLE	DRAWN	LMS 7-25-72	SOLITRON DEVICES INC. TRANSISTOR DIVISION RIVIERA BEACH, FLORIDA
					ONE PLACE 1.01 ± 0.01	DIODE & BASE ASSY	DRAFTING	LMS 7-25-72	
					TWO PLACE 1.001 ± 0.001		ENGINEER	BR 8-14-72	
					THREE PLACE 1.0001 ± 0.0001		APPROVED	EQ 8-14-72	
				FRACTIONAL ±					
				ANGULAR ±					
				MATERIAL	SPE SPEC.	SCALE	4 X SIZE		
						DEVICE	DO - 5		
								DRAWING NUMBER	REV
								TD-4585	



- NOTES:
1. .002 MAX. BURR ALLOWED.
 2. ROLL THREADS TO WITHIN $2\frac{1}{2}$ THREADS OF HEAD.
 3. DIAMETER OF UNTHREADED PORTION OF STEM TO BE .220/.235.



REVISION RECORD				TOLERANCE				DRAWING TITLE				DRAWN				SOLITRON DEVICES INC.			
REV				ONE PLACE	±	0.1	0.001	DRAFTING	LMS	1/14/72		ENGINEER	BR	1/14/72		TRANSISTOR DIVISION			
				TWO PLACE	±	0.01	0.002									RIVIERA BEACH, FLORIDA			
				THREE PLACE	±	0.001	0.002												
				FRACTIONAL	±														
				ANGULAR	±														
				MATERIAL				SPE SPEC.				SCALE							
												4 X SIZE							
												DO-5							

(REF. DWG. N-61960-1)

DRAWING NUMBER
TD-4587

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